[0056] Operation **616** can be an optional operation of flowchart **600**. That is, if the first and second substantially transparent insulating layers can be deposited where it is desired, there is really no need to perform operation **616**. For example, the first and second substantially transparent insulating layers can be deposited over the first and second set of conductive traces in such a manner as to leave exposed electrical contact pad areas of the first and second sets of conductive traces to enable coupling of test equipment and/or sensing circuitry of the capacitive sensing device.

[0057] At operation **618**, if several capacitive sensing devices are being manufactured on a single substantially transparent substrate, the substantially transparent substrate can be cut to separate the capacitive sensing devices. It is appreciated that the cutting at operation **618** can be implemented in diverse ways. For example, a small rotary wheel can be used to roll across the substantially transparent substrate to scratch its surface to enable it to be broken or separated along the scratches. Alternatively, a laser can be used to move across the substantially transparent substrate to provide enough thermal expansion to cut it. However, either of these cutting techniques leaves a fairly square edge that can easily be chipped. As such, each of the cut edges (and others if desired) of the substantially transparent substrate can be edge ground at operation **618** in order to protect the edges of the capacitive sensing device from casual contact damage. The edge grind at operation **618** can be performed to create 45 degree bevels along the desired edges of the substantially transparent substrate. Furthermore, at operation **618**, the dust created by the edge grinding can also be washed away. Once operation **618** is completed, the process exits flowchart **600**. It is noted that operation **618** can be an optional operation of flowchart **600**. For example, if a single capacitive sensing device is being manufactured on a single substantially transparent substrate, there may not be a need to perform operation **618**.

[0058] **FIG. 7** is a cross sectional view of an exemplary capacitive sensing device **700** in accordance with an embodiment of the present invention. It is appreciated that capacitive sensing device **700** may have been manufactured utilizing the process represented by flowchart **200** of **FIG. 2** or flowchart **600** of **FIG. 6**. Specifically, capacitive sensing device **700** includes a substantially transparent substrate **703** having metal layers **701** and **713** which are separated by a substantially transparent insulating material layer **702**. Additionally, a second substantially transparent insulating material layer **704** can be used in order to provide an abrasion resistance layer for metal layer **713**. Metal layers **701** and **713** have each been patterned to provide conductive traces **705**, **707**, **709** and **711** that can be coupled to sensory circuitry (not shown) of capacitive sensing device **700**. It is understood that conductive traces **707** and **709** may also be referred to as electrical contact pads that are located outside of the sensing area (not shown) of capacitive sensing device **700**. It is noted that substantially transparent insulating layers **702** and **704** are each patterned so that electrical contacts can be made to metal layers **701** and **713**.

[0059] Within the present embodiment, conductive traces **705** and **707** have been deposited and patterned above the substantially transparent substrate **703**. It is noted that conductive traces **705** and **707** each includes three layers of material. Specifically, conductive traces **705** and **707** each includes a layer of black chrome **706**, a layer of aluminum **708** and a layer of titanium **710**. Additionally, substantially transparent insulating layer **702** has been deposited above conductive traces **705** and **707** and substantially transparent substrate **703**.

[0060] Within **FIG. 7**, conductive traces **709** and **711** have been deposited and patterned above the substantially transparent insulating layer **702**. It is appreciated that conductive traces **709** and **711** each includes three layers of material. Specifically, conductive traces **709** and **711** each includes a layer of black chrome **712**, a layer of aluminum **714** and a layer of titanium **716**. Furthermore, substantially transparent insulating layer **704** has been deposited above conductive traces **709** and **711** and substantially transparent insulating layer **702**.

[0061] The substantially transparent insulating layer **704** of the capacitive sensing device **700** has been patterned to form an opening **722** above conductive trace **709**. Moreover, substantially transparent insulating layers **704** and **702** have been patterned to form an opening **720** above conductive trace **707**. As such, electrical contact may be made with metal layers **701** and **713**. It is noted that openings **720** and **722** can be located on or near the perimeter of substantially transparent substrate **703**. A user view **718** represents the direction from which users can view the capacitive sensing device **700**. As such, an underlying image or an information display device (not shown) could be located behind the capacitive sensing device **700** facing the user view **718**. In this manner, a user would be viewing the underlying image or information display device through capacitive sensing device **700**. Within the present embodiment, capacitive sensing device **700** is separate from active components used to comprise the information display device.

[0062] Within **FIG. 7**, it is appreciated that aluminum layer **708** and titanium layer **710** of conductive traces **705** and **707** are hidden or obscured by black chrome layer **706** (e.g., chromium oxynitride). Furthermore, aluminum layer **714** and titanium layer **716** of conductive traces **711** and **709** are hidden or obscured by black chrome layer **712**. If black chrome layers **706** and **712** were not included within capacitive sensing device **700**, aluminum layers **708** and **714** may reflect unwanted ambient light towards the user. As such, a black matrix material (e.g., black chrome layers **706** and **712**) is placed between the reflective conductive traces (e.g., **708** and **714**) and the user of capacitive sensing device **700**. The black chrome layers **706** and **712** have low reflectance and high absorbency so that they appear black and return little of the light that impinge onto them. A reactive sputtering of chromium with oxygen and nitrogen can be used to create black chrome layers **706** and **712**. However, other metals and organics like polyimide can also be used to form light absorbing black matrix layers like black chrome layers **706** and **712**. Within one embodiment, black chrome layers **706** and **712** may each be deposited at a depth of 50-100 nanometers (nm) while aluminum layers **708** and **714** may each be deposited at a depth of 1000 nm. Additionally, titanium layers **710** and **716** may each be deposited at a depth of 50 nm. The three materials may be patterned with substantially the same pattern as described herein. Conversely, each layer of the conductive traces **705**, **707**, **709** and **711** may be patterned with a different pattern.

[0063] It is noted that user view **718** can be on the other side of capacitive sensing device **700**. In response to this